

CLEANING AGENT FOR ELECTRONIC MATERIAL

ABSTRACT OF THE DISCLOSURE

A cleaning agent for an electronic material, such as, magnetic disk substrate, flat panel display substrate, and photomask substrate is provided. The cleaning agent is capable of appropriately etching the surface of an electronic material substrate, such as, magnetic disk substrate, flat panel display substrate, and photomask substrate, without damaging the flatness of the surfaces of the substrates. Furthermore, the cleaning agent realizes excellent particle removal effect by improving the dispersion of the particles detached from the surface of the substrates by using a surfactant, thus the manufacturing yield is improved, and high-degree cleaning with very high cleaning rate is achieved in a short time. The cleaning agent for an electronic material contains a surfactant (A), and is characterized in that, at an active ingredient concentration when being used as cleaning solution and at 25°C, the pH value and the oxidation reduction potential (V) [in mV, vsSHE] meet Formula (1):

$$V \leq -38.7 \times \text{pH value} + 550 \quad (1).$$